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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
10/606,834	06/27/2003	Kouji Nakahara	NIT-379	4822	
7590 11/03/2004			EXAM	MINER	
Mattingly, Stanger & Malur, P.C.			DICKEY, THOMAS L		
Suite 370 1800 Diagonal I	Road		ART UNIT	PAPER NUMBER	
Alexandria, VA 22314			2826		

DATE MAILED: 11/03/2004

Please find below and/or attached an Office communication concerning this application or proceeding.

		Applicat	tion No.	Applicant(s)				
		10/606,8	834	NAKAHARA ET AL	NAKAHARA ET AL.			
	Office Action Summary	Examine	er	Art Unit				
		Thomas	L Dickey	2826	مهم			
Period fo	The MAILING DATE of this communic or Reply	ation appears on th	he cover sheet wi	th the correspondence add	iress			
A SH THE - Exte after - If the - If NO - Faill Any	ORTENED STATUTORY PERIOD FO MAILING DATE OF THIS COMMUNIC insions of time may be available under the provisions of SIX (6) MONTHS from the mailing date of this communication of the provision of	CATION. f 37 CFR 1.136(a). In no enication. days, a reply within the statory period will apply and ill, by statute, cause the apply a	event, however, may a re atutory minimum of thirty will expire SIX (6) MON' oplication to become AB	eply be timely filed y (30) days will be considered timely. THS from the mailing date of this cor ANDONED (35 U.S.C. § 133).				
Status								
1)⊠	Responsive to communication(s) filed	on <u>14 September</u>	<u>2004</u> .					
2a) <u></u> ☐	This action is FINAL . 2b	o)⊠ This action is	non-final.					
3)	Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under <i>Ex parte Quayle</i> , 1935 C.D. 11, 453 O.G. 213.							
Disposit	ion of Claims							
5)□ 6)⊠ 7)⊠	Claim(s) <u>1-20</u> is/are pending in the ap 4a) Of the above claim(s) is/are Claim(s) is/are allowed. Claim(s) <u>1,2 and 12-20</u> is/are rejected Claim(s) <u>3-11</u> is/are objected to. Claim(s) are subject to restriction	e withdrawn from c						
Applicat	ion Papers							
10)⊠	The specification is objected to by the The drawing(s) filed on 27 June 2003 in Applicant may not request that any objection Replacement drawing sheet(s) including the oath or declaration is objected to be	is/are: a) accep ion to the drawing(s) he correction is requi	be held in abeyan ired if the drawing(ce. See 37 CFR 1.85(a). s) is objected to. See 37 CFI	` '			
Priority (under 35 U.S.C. § 119							
12)⊠ a)	Acknowledgment is made of a claim for All b) Some * c) None of: 1. Certified copies of the priority do Some * Copies of the priority do Some * Copies of the priority do Some * Copies of the certified copies of application from the International See the attached detailed Office action	ocuments have be ocuments have be the priority docum al Bureau (PCT Ru	en received. en received in Ap nents have been ule 17.2(a)).	oplication No received in this National S	Stage			
Attachmen	• •		A) □ 1-4	ummon (DTO 442)				
2) 🔲 Notic 3) 🔲 Infor	e of References Cited (PTO-892) e of Draftsperson's Patent Drawing Review (PTO nation Disclosure Statement(s) (PTO-1449 or P r No(s)/Mail Date		Paper No(s	ummary (PTO-413))/Mail Date formal Patent Application (PTO- 	.152)			

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DETAILED ACTION

1. The amendment filed 8/19/04 has been entered.

Claim Rejections - 35 USC § 103

- 2. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

Claims 1,2, and 12-20 are rejected under 35 U.S.C. § 103(a) as being unpatentable over SALVATORE et al. (2002/0131466) in view of MURAI et al. ("Lasing characteristics under high temperature operation of 1.55 µm strained InGaAsP/InGaAlAs MQW laser with InAlAs electron stopper layer", Electronics Letters, Volume 31, Issue 24).

With regard to claims 1,12,14,16,18, and 19, Salvatore et al. discloses an optical semiconductor device, being an integrated light source in which a buried ridge type laser structure and an electro-absorption modulator are integrated, comprising an InP substrate 16; a plurality of layers 28-30-32-34-18, stacked on the InP substrate 16, including a multi-quantum well active layer 18 made of GalnAlAs; an GalnAlAs electron-stopping layer 36 (Salvatore et al. calls this layer a "upper carrier confinement layer," note paragraph 0026. Note further that Salvatore et al. explicitly states, in said

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paragraph, that the "upper carrier confinement layer" 36 confines electrons but not light) stacked on the plurality of layers 28-30-32-34-18; an InGaAsP layer 20 including a grating stacked on the GaInAlAs electron-stopping layer 36; wherein a concave depth of the grating included in the InGaAsP layer 20 is smaller than a thickness of the InGaAsP layer 20, an InP cladding layer 38, having the shape of a ridge mesa stripe (InP cladding layer 38 has the same ridge mesa stripe structure as waveguide 22, note figures 1 and 15b), stacked on the InGaAsP layer 20.

With regard to claims 2,13,15,17, and 20, Salvatore et al. discloses an optical semiconductor device, being an integrated light source in which a buried ridge type laser structure and an electro-absorption modulator are integrated, comprising an InP substrate 16; a plurality of layers 28-30-32-34-18, stacked on the InP substrate 16, including a multi-quantum well active layer 18 made of GalnAlAs; an GalnAlAs electron-stopping layer 36 (Salvatore et al. calls this layer a "upper carrier confinement layer," note paragraph 0026. Note further that Salvatore et al. explicitly states, in said paragraph, that the "upper carrier confinement layer" 36 confines electrons but not light. Applicant has made it clear that the electron stopping layer must allow light to reach the grating from the active layer) stacked on the plurality of layers 28-30-32-34-18; an InGaAsP layer 20 including a grating stacked on the GalnAlAs electron-stopping layer 36; wherein a concave depth of the grating included in the InGaAsP layer 20 is smaller than a thickness of the InGaAsP layer 20, an InP spacer layer (no part #, described at paragraph 0027 as the upper of the InP layers in an InP/InGaAsP/InP structure) stacked

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on the InGaAsP layer 20; an InGaAsP etch stopping layer 44 stacked on the InP spacer layer; and an InP cladding layer 46, having the shape of a ridge mesa stripe (InP cladding layer 46 has the same ridge mesa stripe structure as waveguide 22, note figures 1 and 15b), stacked on the InGaAsP etch stopping layer 44.

Note figures 1,2, 15b, and paragraphs 0004-0010 and 0025-0029 of Salvatore et al. Although Salvatore et al. discloses a GaAllnAs electron-stopping layer, Salvatore et al. does not disclose an InAlAs electron-stopping layer. However, Murai et al. discloses an InAlAs electron-stopping layer, note figure 1 of Murai et al. Note also that Murai et al. teaches that because InAlAs has a significant band offset relative to both GaInAlAs and InGaAsP, the result is both an increase in quantum efficiency and a consequent decrease in laser operating temperature. Therefore, it would have been obvious to a person having skill in the art to replace the GaInAsP active layer of Salvatore et al.'s optical semiconductor device with the InAlAs electron-stopping layer such as taught by Murai et al. in order to raise the band offset between the electron-stopping layer and the active region and better confine electrons to the active region to thus increase quantum efficiency and decrease laser operating temperature.

Allowable Subject Matter

3. Claims 3-11 are objected to as being dependent upon a rejected base claim, but would be allowable if rewritten in independent form including all of the limitations of the base claim and any intervening claims.

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Response to Arguments

4. Applicant's arguments with respect to claims 1,2,4,5, and 10-18 have been considered but are moot in view of the new ground(s) of rejection.

Conclusion

5. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Thomas L Dickey whose telephone number is 571-272-1913. The examiner can normally be reached on Monday-Thursday 8-6.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Nathan J Flynn can be reached on 571-272-1915. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

TLD 10/2004

Minhloan Tran
Primary Examiner
Art Unit 2826